

=> d his

(FILE 'HOME' ENTERED AT 09:42:26 ON 21 JAN 2004)

FILE 'REGISTRY' ENTERED AT 09:43:03 ON 21 JAN 2004
L1 STRUCTURE uploaded
L2 QUE L1
L3 6 S L1 SSS SAM
L4 6 S L2 SSS SAM

FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 09:44:18 ON 21 JAN 2004
L5 13 S L4
L6 6 DUPLICATE REMOVE L5 (7 DUPLICATES REMOVED)

FILE 'HOME' ENTERED AT 09:45:09 ON 21 JAN 2004

FILE 'REGISTRY' ENTERED AT 09:48:02 ON 21 JAN 2004
L7 SCREEN 2067
L8 STRUCTURE uploaded
L9 QUE L8 AND L7
L10 0 S L9 SSS SAM

FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 09:48:42 ON 21 JAN 2004
L11 0 S L10

FILE 'HOME' ENTERED AT 09:48:58 ON 21 JAN 2004

FILE 'REGISTRY' ENTERED AT 09:49:27 ON 21 JAN 2004
L12 SCREEN 2067
L13 STRUCTURE uploaded
L14 QUE L13 AND L12
L15 0 S L14 SSS SAM

FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 09:51:32 ON 21 JAN 2004
L16 0 S L15

FILE 'HOME' ENTERED AT 09:51:43 ON 21 JAN 2004

FILE 'REGISTRY' ENTERED AT 09:54:29 ON 21 JAN 2004
L17 SCREEN 2067
L18 STRUCTURE uploaded
L19 QUE L18 AND L17
L20 0 S L19 SSS SAM
L21 SCREEN 2067
L22 STRUCTURE uploaded
L23 QUE L22 AND L21
L24 2 S L23 SSS SAM
L25 SCREEN 2067
L26 STRUCTURE uploaded
L27 QUE L26 AND L25
L28 0 S L27 SSS SAM
L29 SCREEN 2067
L30 STRUCTURE uploaded
L31 QUE L30 AND L29
L32 1 S L31 SSS SAM

=> FIL HCAPLUS, CAPLUS, USPATFULL
COST IN U.S. DOLLARS

FULL ESTIMATED COST

SINCE FILE ENTRY	TOTAL SESSION
3.36	42.40

FILE 'HCAPLUS' ENTERED AT 09:59:08 ON 21 JAN 2004
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.
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FILE 'CAPLUS' ENTERED AT 09:59:08 ON 21 JAN 2004
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.
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FILE 'USPATFULL' ENTERED AT 09:59:08 ON 21 JAN 2004
CA INDEXING COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

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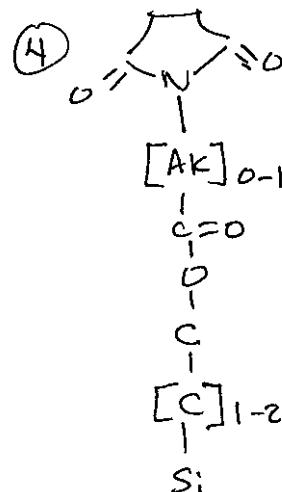
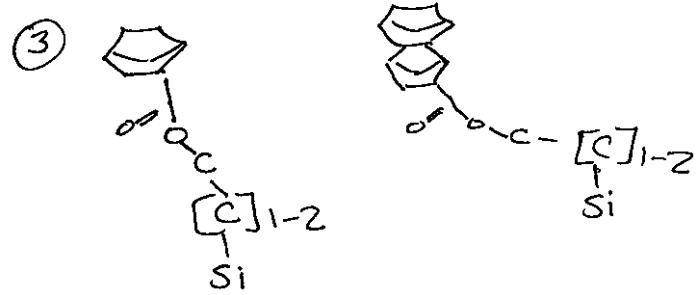
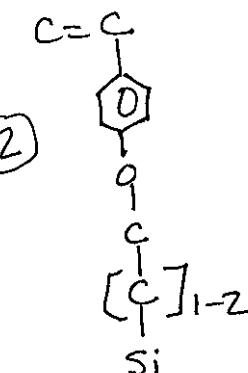
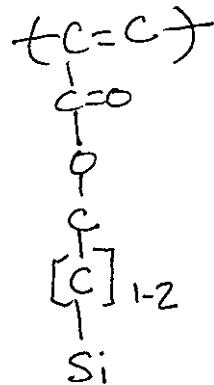
L33 0 L20

=> s 124

L34 11 L24

=> s 128

L35 0 L28



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=> s l32
L36      2 L32

=> s l34 or l36
L37      13 L34 OR L36

=> duplicates remove l37
DUPLICATE PREFERENCE IS 'HCAPLUS, CAPLUS, USPATFULL'
KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n
PROCESSING COMPLETED FOR L37
L38      7 DUPLICATE REMOVE L37 (6 DUPLICATES REMOVED)

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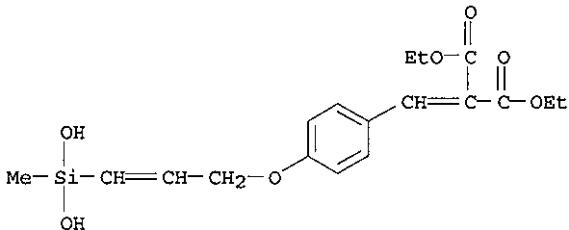
=> d l38 1-7 ibib hitstr

L38 ANSWER 1 OF 7 HCAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 1
ACCESSION NUMBER: 2003:216878 HCAPLUS
DOCUMENT NUMBER: 138:242881
TITLE: Skin cosmetic compositions containing active
 ingredients and specified polysiloxanes
INVENTOR(S): Hayashi, Kyoko; Mitamura, Joji; Tokunaga, Yoshihiro
PATENT ASSIGNEE(S): Lion Corp., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 26 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003081806	A2	20030319	JP 2001-270198	20010906
PRIORITY APPLN. INFO.:			JP 2001-270198	20010906
IT 501947-86-0D	trimethyl-silyl-terminated			
RL: COS (Cosmetic use); BIOL (Biological study); USES (Uses)				
(assumed monomers; skin cosmetic compns. contg. active ingredients and specified polysiloxanes)				
RN 501947-86-0	HCAPLUS			
CN Propanedioic acid, [(4-[[3-(dihydroxymethylsilyl)-2- propenyl]oxyphenyl)methylene]-, diethyl ester, homopolymer (9CI) (CA INDEX NAME)				

CM 1

CRN 208391-14-4
CMF C18 H24 O7 Si



L38 ANSWER 2 OF 7 USPATFULL on STN
ACCESSION NUMBER: 2003:13168 USPATFULL
TITLE: Positive working photoresist composition
INVENTOR(S): Mizutani, Kazuyoshi, Shizuoka, JAPAN
Sato, Kenichiro, Shizuoka, JAPAN
Kodama, Kunihiro, Shizuoka, JAPAN
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Kanagawa, JAPAN (non-U.S.
corporation)

PATENT INFORMATION:	NUMBER	KIND	DATE
APPLICATION INFO.:	US 6506535	B1	20030114
	US 2000-698221		20001030 (9)

PRIORITY INFORMATION:	NUMBER	DATE
	JP 1999-307317	19991028
	JP 1999-331785	19991122
	JP 1999-338487	19991129
	JP 1999-343714	19991202

DOCUMENT TYPE: Utility
FILE SEGMENT: GRANTED
PRIMARY EXAMINER: Baxter, Janet
ASSISTANT EXAMINER: Clarke, Yvette M.

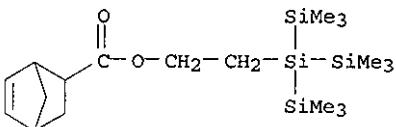
LEGAL REPRESENTATIVE: Sughrue Mion, PLLC
NUMBER OF CLAIMS: 19
EXEMPLARY CLAIM: 1,3
NUMBER OF DRAWINGS: 0 Drawing Figure(s); 0 Drawing Page(s)
LINE COUNT: 2346
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 337954-60-6P
(acid-decomposable polymers for high-soln. pos. photoresists giving rectangular patterns)

RN 337954-60-6 USPATFULL
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-[2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilanyl]ethyl ester, polymer with 2,5-furandione and methyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 337954-57-1
CMF C19 H40 O2 Si4



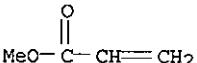
CM 2

CRN 108-31-6
CMF C4 H2 O3



CM 3

CRN 96-33-3
CMF C4 H6 O2



L38 ANSWER 3 OF 7 HCPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 2
ACCESSION NUMBER: 2001:726601 HCPLUS
DOCUMENT NUMBER: 135:280511
TITLE: Positive-working photoresist compositions showing high resolution and high sensitivity and excellent storage stability
INVENTOR(S): Sato, Kenichiro
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 62 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001272784	A2	20011005	JP 2000-385724	200001219
PRIORITY APPLN. INFO.:			JP 1999-363302	A 19991221
			JP 2000-10773	A 20000119
			JP 2000-10774	A 20000119

OTHER SOURCE(S): MARPAT 135:280511

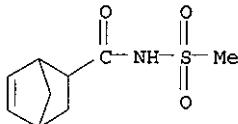
IT 363616-65-3P
RL: PNU (Preparation, unclassified); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(alk.-developing silyl-contg. polymer pos. photoresists having storage stability)

RN 363616-65-3 HCPLUS
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethyl-3-[2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilanyl]propyl ester, polymer with 2,5-furandione and N-(methylsulfonyl)bicyclo[2.2.1]hept-5-ene-2-

carboxamide (9CI) (CA INDEX NAME)

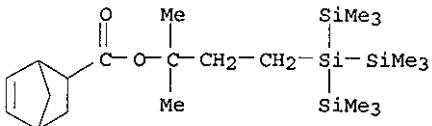
CM 1

CRN 363616-64-2
CMF C9 H13 N O3 S



CM 2

CRN 250589-01-6
CMF C22 H46 O2 Si4



CM 3

CRN 108-31-6
CMF C4 H2 O3



L38 ANSWER 4 OF 7 HCPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 3

ACCESSION NUMBER: 2001:423557 HCPLUS
DOCUMENT NUMBER: 135:38893
TITLE: Positive photoresist compositions for manufacture of semiconductor devices
INVENTOR(S): Sato, Kenichiro; Kodama, Kunihiko; Mizutani, Kazuyoshi
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 66 pp.
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 4
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001159812	A2	20010612	JP 1999-343714	19991202
US 6506535	B1	20030114	US 2000-698221	20001030
PRIORITY APPLN. INFO.:			JP 1999-307317	A 19991028
			JP 1999-331785	A 19991122
			JP 1999-338487	A 19991129
			JP 1999-343714	A 19991202

OTHER SOURCE(S): MARPAT 135:38893

IT 337954-60-6P

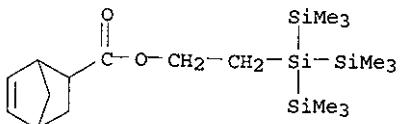
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(acid-decomposable polymers; improvement of exposure margin in pos. photoresists for manuf. of semiconductor devices)

RN 337954-60-6 HCPLUS

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-[2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilanyl]ethyl ester, polymer with 2,5-furandione and methyl 2-propenoate (9CI) (CA INDEX NAME)

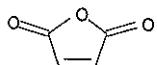
CM 1

CRN 337954-57-1
CMF C19 H40 O2 Si4



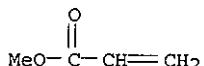
CM 2

CRN 108-31-6
CMF C4 H2 O3



CM 3

CRN 96-33-3
CMF C4 H6 O2



L38 ANSWER 5 OF 7 HCPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 4

ACCESSION NUMBER: 2001:414682 HCPLUS
DOCUMENT NUMBER: 135:26888
TITLE: Alkali-developable positive-working photoresist composition
INVENTOR(S): Sato, Kenichiro; Mizutani, Kazuyoshi
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 71 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 4
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001154361	A2	20010608	JP 1999-338487	19991129
US 6506535	B1	20030114	US 2000-698221	20001030
PRIORITY APPLN. INFO.:			JP 1999-307317	A 19991028
			JP 1999-331785	A 19991122
			JP 1999-338487	A 19991129
			JP 1999-343714	A 19991202

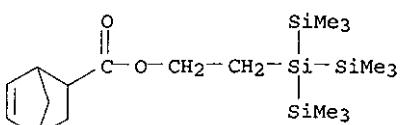
IT 337954-60-6P
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(polymer in alkali-developable pos.-working photoresist compn.)

RN 337954-60-6 HCPLUS

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-[2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilanyl]ethyl ester, polymer with 2,5-furandione and methyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 337954-57-1
CMF C19 H40 O2 Si4



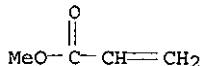
CM 2

CRN 108-31-6
CMF C4 H2 O3



CM 3

CRN 96-33-3
CMF C4 H6 O2



L38 ANSWER 6 OF 7 HCPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 5
ACCESSION NUMBER: 2001:388948 HCPLUS
DOCUMENT NUMBER: 135:12122
TITLE: Positive-working photoresist composition containing sulfonium compound acid generator
INVENTOR(S): Sato, Kenichiro; Mizutani, Kazuyoshi
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 65 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 4
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001147536	A2	20010529	JP 1999-331785	19991122
US 6506535	B1	20030114	US 2000-698221	20001030
PRIORITY APPLN. INFO.:				
		JP 1999-307317	A	19991028
		JP 1999-331785	A	19991122
		JP 1999-338487	A	19991129
		JP 1999-343714	A	19991202

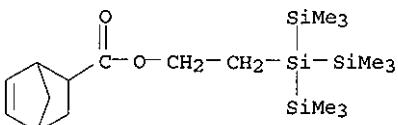
OTHER SOURCE(S): MARPAT 135:12122

IT 337954-60-6P
RL: PNU (Preparation, unclassified); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(photoresist compn. contg. sulfonium compd. acid generator,
acid-decomposable polymer, basic compd. and surfactant)

RN 337954-60-6 HCPLUS
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-[2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilanyl]ethyl ester, polymer with 2,5-furandione and methyl 2-propenoate (9CI) (CA INDEX NAME)

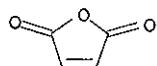
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CMF C19 H40 O2 Si4



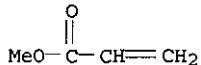
CM 2

CRN 108-31-6
CMF C4 H2 O3



CM 3

CRN 96-33-3
CMF C4 H6 O2



L38 ANSWER 7 OF 7 HCPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 6

ACCESSION NUMBER: 2001:336598 HCPLUS
 DOCUMENT NUMBER: 134:346473
 TITLE: High-resolution positive photoresist compositions
 INVENTOR(S): Mizutani, Kazuyoshi
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 60 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 4
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001125272	A2	20010511	JP 1999-307317	19991028
US 6506535	B1	20030114	US 2000-698221	200001030
PRIORITY APPLN. INFO.:			JP 1999-307317 A	19991028
			JP 1999-331785 A	19991122
			JP 1999-338487 A	19991129
			JP 1999-343714 A	19991202

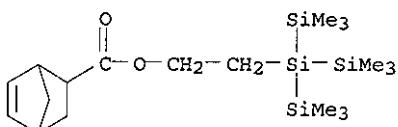
IT 337954-60-6P
 RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (acid-decomposable polymers for high-soln. pos. photoresists giving rectangular patterns)

RN 337954-60-6 HCPLUS

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-[2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilanyl]ethyl ester, polymer with 2,5-furandione and methyl 2-propenoate (9CI) (CA INDEX NAME)

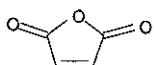
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CRN 337954-57-1
 CMF C19 H40 O2 Si4



CM 2

CRN 108-31-6
 CMF C4 H2 O3



CM 3

CRN 96-33-3
 CMF C4 H6 O2

